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# THE PREPARATION AND PROPERTIES OF SOME PHENOXYARYLSILANES

## M.Černý

Institute of Chemical Process Fundamentals, Czechoslovak Academy of Sciences, 165 02 Prague - Suchdol

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The synthesis of the silanes of type o-, m-, and  $p-C_6H_5-O-C_6H_4Si(C_6H_5)_2X$  (X = Cl, H, CH<sub>3</sub>, OCH<sub>3</sub>, C<sub>2</sub>H<sub>5</sub>, and OC<sub>2</sub>H<sub>5</sub>) is reported. The phenoxy group in the *meta* position substantially decreases melting points of these compounds compared to the *ortho* or *para* derivatives. The thermal and oxidation stability of the compounds was investigated by thermogravimetric analysis.

The use of thermally and oxidation stable substances that are increasingly applied as lubricants for elevated temperatures, hydraulic, heat-transfer or high-vacuum liquids *etc.*, is among others conditioned by their liquid state at ambient temperature. Within the framework of investigation of organosilicon compounds that might find this application, it was expedient to ascertain how the phenoxy group affects melting points of some arylsilanes taken as model compounds. With tetraphenylsilane (m.p.  $236 \cdot 5 - 237^{\circ}$ C (ref.<sup>1</sup>), the *ortho* and *para* substitution by one phenoxy group lowers melting point to  $145 - 146^{\circ}$ C (ref.<sup>2</sup>) and  $165 - 169^{\circ}$ C (ref.<sup>3</sup>), respectively, whilst the same group when attached to the *meta* position brings melting point down to  $37^{\circ}$ C (ref.<sup>4</sup>). Additional phenoxy groups, both in *ortho, para*, and *meta* positions do not decrease melting point significantly.

The aim of this study was to ascertain how the phenoxy group in the *ortho, meta* or *para* position of one phenyl group of some triphenylsilanes of the type  $(C_6H_5)_3$ . SiX (X = Cl, H, CH<sub>3</sub>, OCH<sub>3</sub>, C<sub>2</sub>H<sub>5</sub>, and OC<sub>2</sub>H<sub>5</sub>) affects together with expected increase of their boiling point also their melting point, volatility and oxidation stability at elevated temperatures.

The compounds under study were prepared by reaction of *o*-, *m*-, and *p*-phenoxyphenylmagnesium bromides with diphenyldichlorosilane, followed by treating the products, *o*-, *m*-, and *p*-phenoxyphenyldiphenylchlorosilanes, with methylmagnesium bromide, ethylmagnesium bromide, methanol or ethanol. *o*-, *m*-, and *p*-Phenoxyphenyldiphenylsilanes were prepared by reduction of the chlorosilanes with sodium bis(2-methoxyethoxy)aluminium hydride. The compounds prepared are presented in Table I. The purity of the above compounds was verified by NMR spectroscopy.

The effect of the introduction of the phenoxy group to the *ortho*, *meta* or *para* position of the phenyl group of the parent compound,  $(C_6H_5)_3SiX$ , is demonstrated by data given in Table I. With triphenylmethylsilane, triphenylmethoxysilane, triphenylethylsilane, and triphenylethoxysilane, the *ortho* substitution by phenoxy

×	$Ph_3SiX^a$	$o ext{-PhOC}_{6} ext{H}_{4} ext{SiPh}_{2} ext{X}$	$m$ -PhOC $_6H_4$ SiPh $_2X$	<i>p</i> -PhOC <sub>6</sub> H <sub>4</sub> SiPh <sub>2</sub> X
CI	94-95, 97, 104-5			
	105-8, 110-111	6616	q	q
Н	36 - 37, 40 - 43	q	ą	53.5-54.5
$CH_3$	67, 69.5-69.9	9697	64-65	47-48
C <sub>2</sub> H <sub>5</sub>	68-70, 72-74, 76 89-91	9192	٩	69•5-70
0CH <sub>3</sub>	52—55, 54, 5—55 42—43, 55	87—88	ę	Ą
$OC_2H_5$	63, 65	99·0-99·5	ų	61 - 92

group brings about a melting point increase of max.  $30^{\circ}$ C. With triphenylsilane and triphenylchlorosilane, there is a slight melting point decrease. Analogous substitution in the *para* position leads to melting point increase with triphenylsilane and triphenylethoxysilane, whilst no change is observed with triphenylethylsilane; melting point decreases with triphenylmethylsilane and triphenylmethoxysilane. Melting point depression is greatest for the *meta* derivatives, *m*-phenoxyphenyldiphenylethyl-, -ethoxy-, and -methoxysilane being liquids at room temperature. Melting point decreases only slightly upon the *meta* substitution of the phenyl group of triphenyl-methylsilane with phenoxy group. In the case of triphenylsilane, the introduction of phenoxy group to the *ortho*, *meta* or para position leads to melting point decrease, whilst with triphenylchlorosilane this decrease is observed for the *meta* and *para* derivatives.

The thermal and oxidation stability of the compounds prepared was examined by thermogravimetric analysis, following weight loss during even heating of the sample in a stream of nitrogen of air. From Table II it is seen that in a nitrogen atmosphere the most volatile compound is *p*-phenoxyphenyldiphenylsilane, followed by *p*-phenoxyphenyldiphenylmethylsilane, the least volatile being *p*-phenoxyphenyldiphenylethoxy- and -ethylsilane. In a stream of air, p-phenoxyphenyldiphenylsilane undergoes oxidation decomposition under formation of a large amount of distillation residue (17%). p-Phenoxyphenyldiphenylmethylsilane decomposes partially to both the more and less volatile components, as indicated by the course of weight loss of the sample compared to that observed on heating in a nitrogen atmosphere. p-Phenoxyphenyldiphenylsilane decomposes also in air (11% residue). Of the phenoxyphenyldiphenylethylsilanes, the most volatile is the ortho derivative, followed by the meta and para isomer (3 and 5% residue, respectively). Summarizing, the least thermally and oxidation stable are the substances containing Si-H bond, then those containing  $Si - OC_2H_5$  bonds, and finally those with  $Si - C_2H_5$  bonds. Of the individual isomers, the most stable one is *p*-phenoxyphenyldiphenylethylsilane that does not decompose to 240°C.

#### EXPERIMENTAL

In preparing the starting compounds, p-phenoxybromobenzene, b.p.  $162-165^{\circ}/14$  Torr, m-phenoxybromobenzene, b.p.  $110-115^{\circ}C/0.5$  Torr, and o-phenoxybromobenzene, b.p.  $115-117^{\circ}C/0.6$ Torr, m.p.  $43-44^{\circ}C$  (methanol), the great attention was paid to their purity. As p-phenoxybromobenzene when prepared by usual bromination of diphenyl ether, contains admixture of the ortho derivative<sup>7</sup>, it was obtained by Ullmann reaction<sup>8</sup> from p-dibromobenzene and sodium phenolate. o-Phenoxybromobenzene was prepared in a similar fashion from o-dibromobenzene. The pure m-phenoxybromobenzene was synthesized in the following way. Bromination of nitrobenzene afforded m-bromonitrobenzene<sup>9</sup> which in turn was reduced to m-bromoaniline<sup>10</sup>. This compound was converted by Sandmayer reaction<sup>11</sup> to m-dibromobenzene which by treating with sodium phenolate<sup>12</sup> afforded the pure m-phenoxybromobenzene.

TABLE II Amounts of Compounds (%) at Various Temperatures (°C) on Their Heating in a Stream of Nitrogen <sup><i>a</i></sup> or Air <sup><i>b</i></sup>	iures (	°C) on	Their H	eating in	a Strea	m of Nit	trogen <sup>a</sup> c	or Air <sup>b</sup>				
Compounds		200	220	240	260	280	300	320	340	360	380	395
· p-Phenoxyphenyldiphenylsilane	b b	100 100	99 100	97 99	94 97	86 91	71 78	38 54	5 31	0 20		17
p-Phenoxyphenyldiphenylmethylsilane	$^{a}_{b}$	100 100	100 100	96	94 95	84 90	60 80	24 63	0 36	m	) <b>0</b>	
p-Phenoxyphenyldiphenylethoxysilane	p	100 100	66 86	97 96	94 94	90 90	78 81	60 64	35 40	4	0 12	- 11
p-Phenoxyphenyldiphenylethylsilane	b	100 100	100 100	100 100	97 98	93 95	82 88	63 72	38 53	2 21	5	5
<i>m</i> -Phenoxyphenyldiphenylethylsilane <i>o</i> -Phenoxyphenyldiphenylethylsilane	a a	100	100 99	99 86	97 90	90 81	76 63	50 28	16 2	4 0	С	ن ا

The purity of all compounds was verified by gas chromatography. <sup>1</sup>H-NMR spectra were recorded on Tesla B 477 spectrometer. Melting points were determined with Koefler hot stage microscope and are uncorrected.

The instrument for thermogravimetric analysis was made according to the scheme described in the work<sup>13</sup>. The procedure used was the same as in the previous work<sup>14</sup>, with the exception that the sample was heated with a rate of  $6^{\circ}$ C per min. Samples weighed 70-90 mg. It was found by calibration that for such samples the quartz spiral prolongation is proportional to their weight; with 100 mg load it was 9.4 mm.

p-Phenoxyphenyldiphenylchlorosilane. The Grignard reagent prepared from  $25 \cdot 2$  g (0·101 mol) of *p*-phenoxybromobenzene and  $2 \cdot 9$  g of magnesium powder in 100 ml of tetrahydrofuran was added dropwise with stirring to  $38 \cdot 0$  g (0·15 mol) of diphenyldichlorosilane in 100 ml of benzene over a period of 20 min. The reaction mixture was heated to reflux and the solvents were partially removed by distillation. After 100 ml of dry xylene were added, solvent removal was continued until the reaction mixture temperature reached a boiling point of xylene. The mixture was then refluxed for another 2 h. The inorganic salts that precipitated during solvent removal were filtered off after cooling the mixture in an inert gas atmosphere and then were washed with benzene. The filtrate was condensed. Twofold distillation afforded  $26 \cdot 1$  g ( $66 \cdot 6\%$ ) of *p*-phenoxyphenyl-diphenylchlorosilane, b.p. 195–198°C/0·3 Torr.

o-*Phenoxyphenyldiphenylchlorosilane*, b.p.  $190-193^{\circ}$ C/0.5 Torr, m.p.  $97-99^{\circ}$ C, was obtained similarly in 82% yield with the exception that the Grignard reagent was added to a xylene solution of diphenyldichlorosilane.

m-Phenoxyphenylchlorosilane, b.p.  $191-195^{\circ}C/0.3$  Torr, was obtained in 88% yield by the procedure used to prepare the othro derivative.

p-Phenoxyphenyldiphenylsilane. p-Phenoxyphenyldiphenylchlorosilane (3.9 g, 0.01 mol) dissolved in benzene was reduced with an excess of 70% benzene solution of NaAlH<sub>2</sub>(OCH<sub>2</sub>CH<sub>2</sub>. .OCH<sub>3</sub>)<sub>2</sub>. After 15 min boiling, the reaction mixture was cooled and decomposed with 20% sulphuric acid. The benzene layer was separated, washed with aqueous sodium hydrogen carbonate and dried with calcium chloride. Distillation afforded 3.2 g (91%) of p-phenoxyphenyldidiphenylsilane, b.p. 186–188°C/0.3 Torr; m.p. 53.5–54.5°C (acetone). For C<sub>24</sub>H<sub>20</sub>OSi (352.5) calculated: 81.77% C, 5.72% H; found: 81.70% C, 6.00% H. NMR spectrum: a multiplet of aromatic protons at  $\delta = 7.877$  to 6.768, a singlet (Si—H) at  $\delta = 5.626$ . The structure was confirmed by spectrum integration.

o-Phenoxyphenyldiphenylsilane, b.p.  $180-182^{\circ}C/0.5$  Torr, was obtained similarly. Found 81.46% C, 5.76% H. NMR spectrum: a multiplet of aromatic protons centered at  $\delta$  6.77 and a singlet (Si—H) at  $\delta = 5.6$ . The integrated spectrum confirmed the above structure. Cyclohexane was used as internal standard.

m-Phenoxyphenyldiphenylsilane, b.p.  $176-178^{\circ}C/0.3$  Torr. NMR spectrum: a multiplet of aromatic protons centered at  $\delta = 6.77$ , a singlet (Si-H) at  $\delta = 5.10$ . Internal standard was cyclohexane. Integration of the spectrum confirmed the suggested structure.

p-Phenoxyphenyldiphenylmethylsilane. An excess of methylmagnesium bromide in diethyl ether was added to a solution of 2·1 g of p-phenoxyphenyldiphenylchlorosilane in tetrahydrofuran. After a 3 h. heating to reflux, the reaction mixture was decomposed with dilute sulphuric acid, the ether layer was shaken with aqueous sodium hydrogen carbonate solution and dried with calcium chloride. Distillation gave 1·70 g (86%) of p-phenoxyphenyldiphenyldiphenylmethylsilane, b.p.  $195-197^{\circ}C/0.5$  Torr, m.p.  $47-48^{\circ}C$  (methanol). Recorded<sup>15</sup> b.p.  $212^{\circ}C/0.07$  Torr and the

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temperature of liquidity  $-2^{\circ}$ C. For C<sub>25</sub>H<sub>22</sub>OSi (366·5) calculated: 81·92% C, 6·05% H; found: 81·84% C, 6·21% H. Its structure was confirmed by <sup>1</sup>H-NMR spectroscopy.

o-Phenoxyphenyldiphenylmethylsilane was obtained similarly in 81% yield. B.p.  $170-171^{\circ}C/0.4$ Torr, m.p.  $96-97^{\circ}C$  (ethanol). Recorded<sup>15</sup> b.p.  $198^{\circ}C/0.04$  Torr and m.p.  $95^{\circ}C$ . Found: 81.96% C, 6.03% H. NMR spectrum: a multiplet of aromatic protons at  $\delta = 6.435-7.686$ , a singlet of Si--CH<sub>3</sub> protons at  $\delta = 0.780$ . Hexamethyldisilane was used in capillary tube as external standard. The spectrum integration confirmed the suggested structure.

m-Phenoxyphenyldiphenylmethylsilane was obtained similarly in 85% yield. B.p.  $180-182^{\circ}C/(0.3 \text{ Torr, m.p. } 64.0-65.0^{\circ}C \text{ (methanol). Recorded}^{15} \text{ b.p. } 196^{\circ}C/0.02 \text{ Torr, the temperature of liquidity } 4^{\circ}C$ . Found: 81.92% C, 5.97% H.

p-Phenoxyphenyldiphenylethylsilane was obtained from p-phenoxyphenyldiphenylchlorosilane and ethylmagnesium bromide in 80% yield. B.p.  $198-201^{\circ}C/0.5$  Torr, m.p.  $69.5-70^{\circ}C$ . For  $C_{26}H_{24}OSi$  (380.6) calculated: 82.06% C, 6.36% H; found: 81.87% C, 6.41% H. NMR spectrum: a multiplet of aromatic protons centered at  $\delta = 7.59$  and unresolved multiplet of Si $-C_2H_5$ protons centered at  $\delta = 1.435$ . Hexamethyldisilane was used as external standard. Integration of the spectrum confirmed the suggested structure.

o-Phenoxyphenyldiphenylethylsilane was prepared similarly in 91% yield, b.p.  $173 - 174^{\circ}C/0.4$ Torr, m.p.  $91 - 92^{\circ}C$  (ethanol). Found: 81.92% C, 6.18% H. NMR spectrum agreed with the suggested structure. A multiplet of aromatic protons was found at  $\delta = 7.235$ ; unresolved multiplet of Si-C<sub>2</sub>H<sub>5</sub> protons was located at  $\delta = 1.15$ . External standard was hexamethyldisilane.

m-Phenoxyphenyldiphenylethylsilane. Yield 88%, b.p. 184–186°C/0·4 Torr. Found: 81·84% C, 6·53% H. Its structure was confirmed by NMR spectroscopy.

p-Phenoxyphenyldiphenylmethoxysilane. A solution of the Grignard reagent prepared from 39.9 g (0.16 mol) of p-phenoxybromobenzene and 4.28 g (0.176 mol) of magnesium in 100 ml of diphenyl ether was added slowly with stirring to a solution of 39.8 g (0.16 mol) of diphenyl-methoxychlorosilane in 250 ml of benzene. After removal of the ether by distillation, light petro-leum ether was added in excess to the reaction mixture. Inorganic salts were filtered off with suction and washed with benzene. The filtrate was condensed and distilled to give 31.6 g of the product, b.p.  $205-210^{\circ}$ C/0.5 Torr. For C<sub>25</sub>H<sub>22</sub>O<sub>2</sub>Si (382.5) calculated: 7.34% Si, 78.49% C, 5.80% H; found: 7.43% Si. NMR spectrum: a multiplet of aromatic protons at  $\delta = 6.516-7.739$  with maximum at  $\delta = 7.172$  and a singlet methoxy protons at  $\delta = 3.439$ . External standard was hexamethyldisiloxane. The structure was confirmed by integration.

o-Phenoxyphenyldiphenylmethoxysilane. A solution of 3.80 g (9.83 mmol) of o-phenoxyphenyldiphenylchlorosilane in 10 ml od benzene was mixed with a solution of 0.64 g (20 mmol) of absolute methanol and 0.80 g (10.1 mmol) of pyridine in 10 ml of benzene. Immediately after the mixing the precipitate pyridine hydrochloride appeared. This was filtefed off after standing overnight and then washed with benzene. The filtrate was condensed under reduced pressure, a distillation residue was dissolved in benzene and the hydrochloride admixture was removed by filtration. The solvents were partially evaporated and the residue distilled to give 3.1 g (82.5%) of the product, b.p. 200-210°C/0.4 Torr (bath temperature), m.p. 87-88°C (methanol). Found: 78.35% C, 5.54% H. NMR spectrum: a multiplet of aromatic protons at  $\delta = 6.222-7.812$  with maximum at  $\delta = 7.213$  and a singlet of methoxy protons at  $\delta = 3.515$ . Integration of the spectrum confirmed the suggested structure. Internal standard was 30% solution of hexamethyldisiloxane in CCl<sub>4</sub>.

m-Phenoxyphenyldiphenylmethoxysilane was obtained in 86% yield in a similar fashion as the ortho derivative, b.p.  $182 - 184^{\circ}$ C/0·4 Torr. Found: 7·45% Si. NMR spectrum: a multiplet of aro-

matic protons centered at  $\delta = 7.19$ , a singlet of methoxy protons at  $\delta = 3.52$ . Internal standard was cyclohexane. The integral agreed with the structure suggested.

p-Phenoxyphenyldiphenylethoxysilane was obtained in 63% yield by reaction of the chlorosilane with ethanol in the presence of pyridine. M.p.  $91-92^{\circ}C$  (ethanol). For  $C_{26}H_{24}O_{2}Si$  (396.6) calculated: 78.75% C, 6.10% H; found: 78.61% C, 6.14% H. NMR spectrum confirmed the structure.

o-Phenoxyphenyldiphenylethoxysilane was obtained in 77% yield by treating the chlorosilane with ethanol in the presence of pyridine. M.p. 99–100°C (ethanol). Found 78.98% C, 6.04% H. NMR spectrum: a triplet of methyl protons of the ethoxy group centered at  $\delta = 1.435$ , a quadruplet of the methylene protons centered at  $\delta = 4.059$  and a multiplet of aromatic protons centered at  $\delta = 7.52$ . Internal standard was hexamethylsilane. Integration of the spectrum confirmed the structure.

m-Phenoxyphenyldiphenylethoxysilane was prepared similarly and obtained in 87% yield. B.p. 184–186°C/0.4 Torr. Found 78.57% C, 6.08% H. NMR spectrum: a triplet of methyl protons of the ethoxy group centered at  $\delta = 1.1$ , a quadruplet of the methylene protons centered at  $\delta = 3.77$  and a multiplet of aromatic protons at  $\delta = 7.19$ . The structure was confirmed by integration of the spectrum.

#### REFERENCES

- 1. Spialter L., Priest D. C., Harris C. W.: J. Amer. Chem. Soc. 77, 6227 (1955).
- 2. Oita K., Gilman H.: J. Org. Chem. 21, 1009 (1956).
- 3. Meston A. M., Thompson J. M. C.: Unpublished results.
- 4. Aftergut S., Brown G. P.: Chem. Ind. (London) 1959, 1091.
- 5. Bažant V., Chvalovský V., Rathouský J.: Organosilicon Compounds. Academia, Prague 1965.
- Bažant V., Chvalovský V., Rathouský J.: Organosilicon Compounds. Publication of the Institute of Chemical Process Fundamentals of the Czechoslovak Academy of Sciences, Prague 1973.
- 7. Bachvalov O. V., Koptyug V. A.: Zh. Org. Khim. 5, 331 (1969).
- 8. Ullmann F., Sponagel P.: Ann. 350, 83 (1906).
- 9. Johnson J. R., Gauerke C. G.: Org. Syn. Coll. Vol. I, p. 123. Wiley, New York.
- 10. Natelson S., Gottfried S. P.: J. Amer. Chem. Soc. 61, 1001 (1939).
- 11. Mathieson D. W., Newbery G.: J. Chem. Soc. 1949, 1133.
- 12. Gilman H., Marrs O. C.: J. Org. Chem. 25, 1194 (1960).
- 13. Igarashi S., Mita I., Kambe H.: J. Appl. Polymer Sci. 1964, 1455.
- 14. El-Attar A. A. A., Černý M.: This Journal, in press.
- 15. Fink W : Helv. Chim. Acta 56, 355 (1973).

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